

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: To be Assigned

Examiner: To be Assigned

#2A
NEAC

In Re PATENT APPLICATION Of:

Applicant : Minoru WATANABE

Appln. No. : Continuation of Serial No. 09/443,500

Filed : Herewith

For : METHOD AND APPARATUS FOR
FORMING RESIST PATTERN

Attorney Ref. : MAE 223 C1

PRELIMINARY
AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Preliminary to examination, please amend the application as follows:

IN THE SPECIFICATION:

Please amend page 1 of the specification to read as follows:

--This application is a continuation of application serial number 09/443,500, which
was filed on November 19, 1999.--

IN THE CLAIMS

Please cancel claims 2-4 without prejudice or disclaimer to the subject matter
recited therein.

Please amend claim 1 as follows:

1. (Amended) A method of forming a resist pattern on a semiconductor
substrate, comprising:
forming a resist film on the semiconductor substrate;
supplying a developing solution on the resist film to remove the resist film, wherein
a portion of the resist film remains on the semiconductor substrate; and